

Title (en)  
REACTIVE ION ETCHING PROCESS FOR ETCHING METALS

Title (de)  
REAKTIVIONENÄTZVERFAHREN ZUM ÄTZEN VON METALLEN

Title (fr)  
TRAITEMENT DE GRAVURE IONIQUE RÉACTIVE POUR GRAVER DES MÉTAUX

Publication  
**EP 2205775 A1 20100714 (EN)**

Application  
**EP 07815243 A 20070926**

Priority  
AU 2007001425 W 20070926

Abstract (en)  
[origin: WO2009039552A1] A method of etching a metal by a reactive ion etching process is provided. The etchant gas chemistry for the reactive ion etching process consists essentially of NH<sub>3</sub>. The process is particularly suitable for etching superalloys, which etch only slowly using conventional metal etching techniques.

IPC 8 full level  
**C23F 1/12** (2006.01); **H01L 21/306** (2006.01); **H01L 21/3065** (2006.01)

CPC (source: EP)  
**B41J 2/14056** (2013.01); **B41J 2/1603** (2013.01); **B41J 2/1628** (2013.01); **B41J 2/1631** (2013.01); **B41J 2/1642** (2013.01); **C23F 4/00** (2013.01); **B41J 2002/1437** (2013.01); **B41J 2002/14387** (2013.01); **B41J 2002/14475** (2013.01)

Citation (search report)  
See references of WO 2009039552A1

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Designated extension state (EPC)  
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**AU 2007001425 W 20070926**; EP 07815243 A 20070926; TW 97105896 A 20080220